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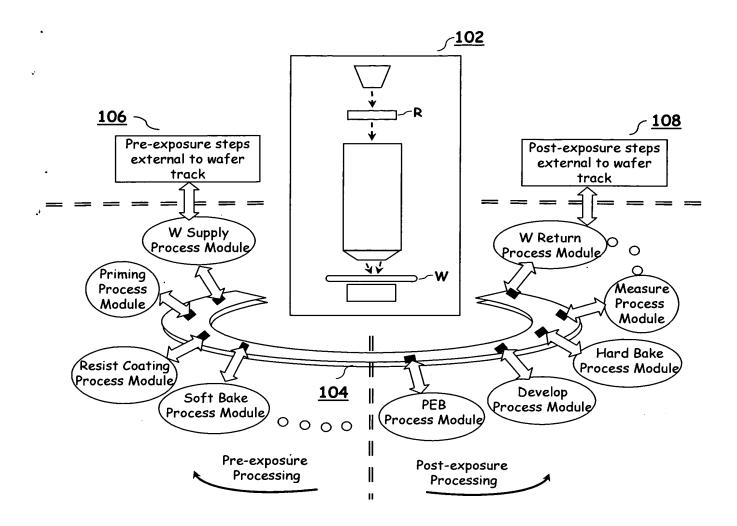
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100

FIG. 1A

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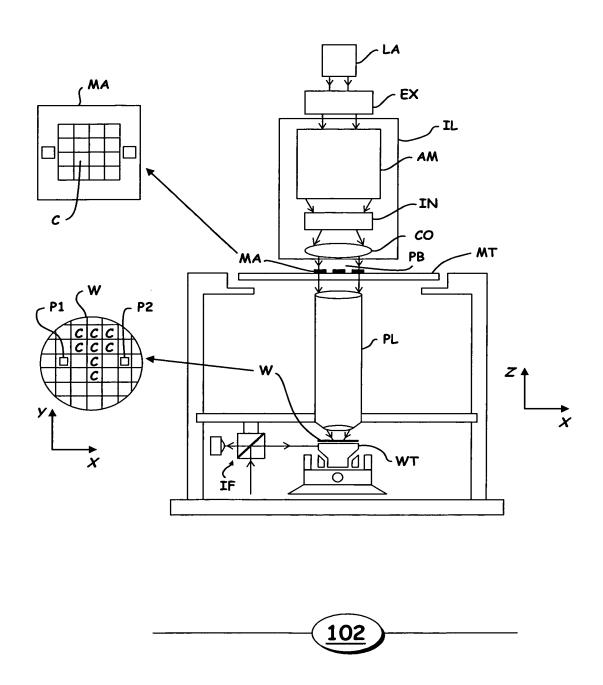
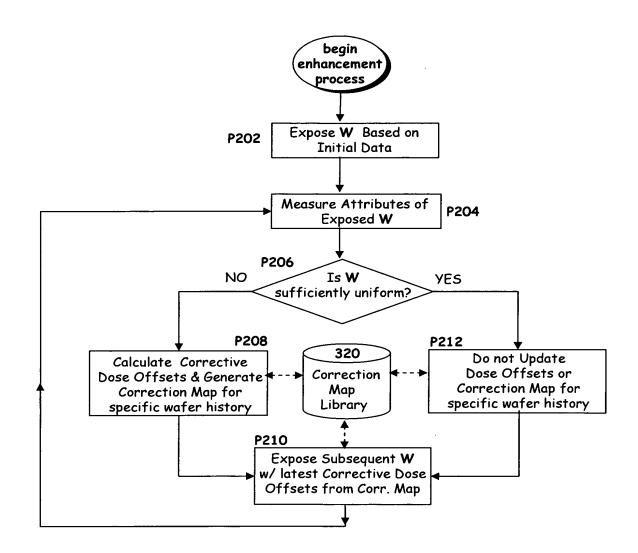


FIG. 1B

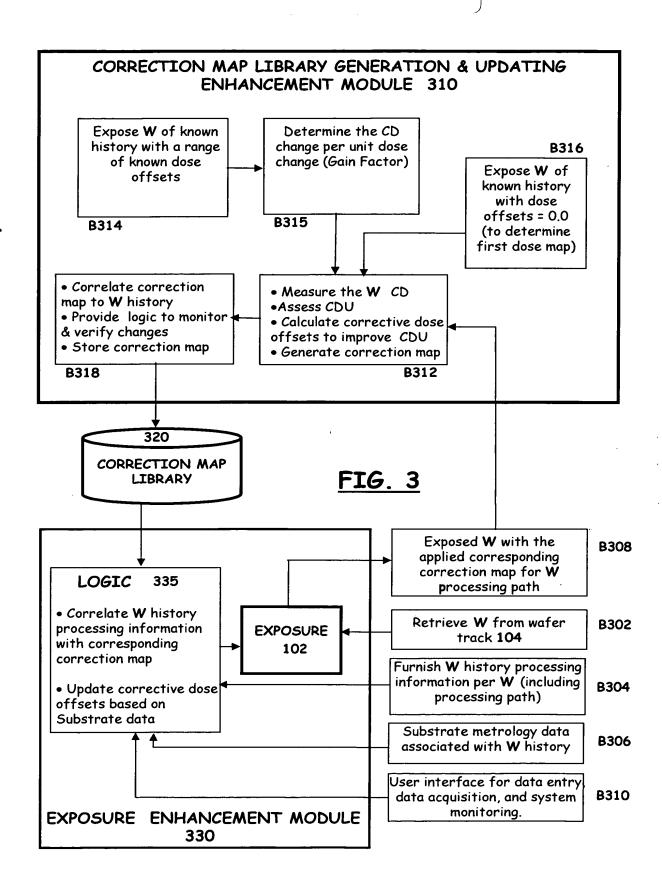
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<u> 200</u>

FIG. 2

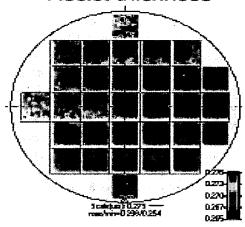
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Examples Pre Exposure Substrate Metrology Data (B306)

Resist thickness



BARC Thickness

FIG. 4A

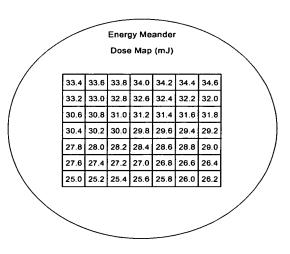
FIG. 4B

SCAR # 0000

0.605

0.50

Example Wafer Dose Layout & Range (B314)



Example CD Change per Unit Dose (B315)

UV210 / AR2 /850 Annular 80 85/55 110nm 1:1 [-7.2nm / mJ] 140 135 130 125 120 8 115 110 y = -7.2288x + 348.44 105 $R^2 = 0.9632$ 100 30 30.5 31.5 32 33.5 Dose (mJ) nm/mJ — Linear (nm/mJ)

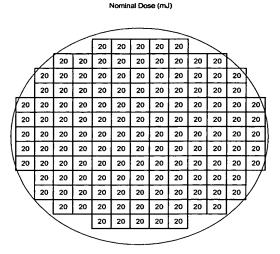
FIG. 4C

FIG. 4D

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Example Initial Dose Map: Dose Offset = 0 (B316)

Example CD Results: with Dose Offset = 0 (B312)



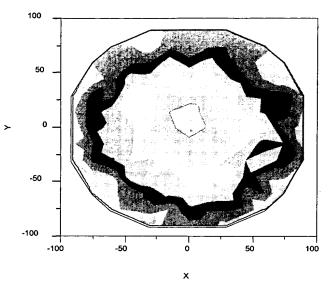
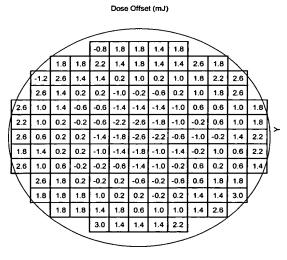


FIG. 4E

FIG. 4F

Example Wafer Dose Layout with Dose Offset (B308)

Example CD Results: with Applied Dose Offset (B312)



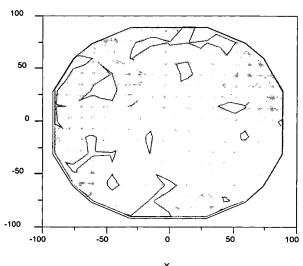


FIG. 46

FIG. 4H